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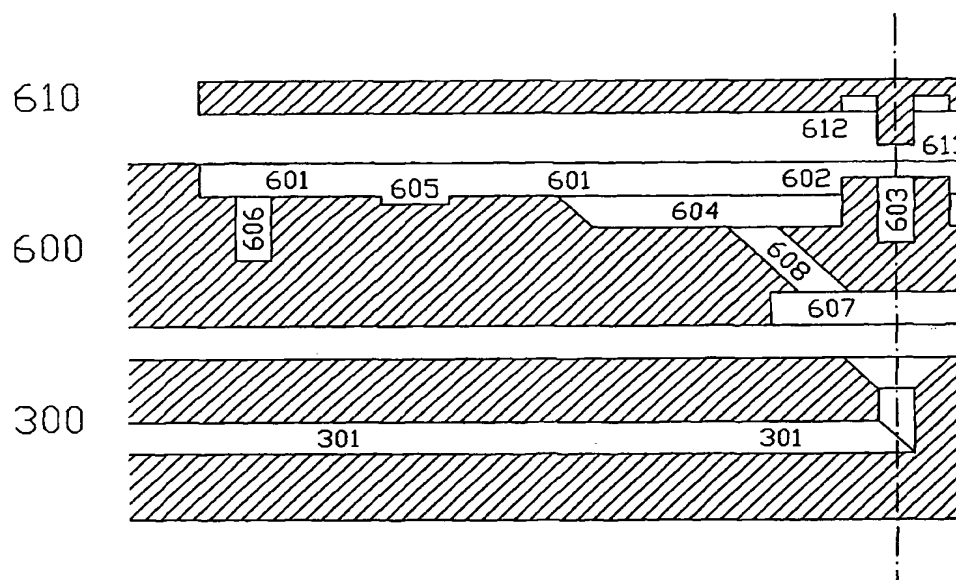
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(54) Title: SUPPORT SYSTEM FOR A TREATMENT APPARATUS



(57) Abstract: A system for an apparatus of the type adapted to treat substrates and/or wafers is described and comprises a stationary base element (600) and a movable support (610) for at least one substrate or at least one wafer, the support being rotatable above the element (600) about a stationary axis; a chamber (610), and at least one duct (608) is provided for the admission of at least one gas-flow to the chamber (604) in order to raise the support (610); the system also comprises means (605) for converting the flow of gas into the chamber (604) into rotation of the support (610).

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